

50. The photoresist of claim 43 wherein the non-hydrolytic solvent is propylene glycol methyl ether acetate.

51. The photoresist of claim 50 wherein the photoresist composition contains less than about 2 weight percent of a hydroxylic solvent, based on total weight of the composition.

52. A method for forming a photoresist relief image onto a substrate comprising:
a) applying a coating layer of a photoresist composition of claim 1 on a substrate;
and
b) exposing and developing the photoresist coating layer to provide a photoresist relief image of the photoresist composition.

53. An article of manufacture comprising a substrate having coated thereon the photoresist of claim 1.

54. The article of claim 53 wherein the substrate is a microelectronic wafer.

REMARKS

Claims 1-26 and 31-42 have been cancelled without prejudice, and claims 43-54 have been added. No new matter has been added by virtue of the amendments. For instance, support for the new claims appears in the original claims of the application.

Applicants respond as follows to the prior Office Action in this case.

Claims 1-11, 17, 19-26, 31-36 and 40-42 were rejected under 35 U.S.C. 103 over Ohsawa et al. (U.S. Patent 5,847,218).

Claims 1-26 and 31-42 were rejected under 35 U.S.C. 103 over Sinta et al. (U.S. Patent 5,731,364).

Claims 1-9, 15-17, 19-26, and 31-42 were rejected under 35 U.S.C. 103 over Aoai et al. (U.S. Patent 5,693,452).

For the sake of brevity, the three rejections are addressed in combination. The rejections are each traversed.

While Applicants disagree with the rejections, it is also believed that the rejections based on the Ohsawa et al. and Aoai et al. have been obviated by the amendments made herein.

In particular, new independent claim 43 recites features of prior claims 12 and 14, which claims were not rejected over the Ohsawa et al. and Aoai et al. documents.

The Sinta et al. document does not disclose the present claimed subject matter in a manner sufficient to sustain the instant Section 103 rejection.

For instance, in the examples of the Sinta et al. document, the only photoresist solvent used is ethyl lactate (only), which is not a non-hydroxylic solvent. See Sinta patent at column 18, lines 59-65.

At column 11, lines 10-24 of the Sinta patent, a rather extensive list of photoresist solvents are identified. No suggestion is seen to select a solvent as Applicant claims, or the good results that would be provided by that selection, as is specifically demonstrated in the examples of the present application.

Sinta et al. also does not disclose use of the lipophilic substituents as recited in the present claims, i.e. one or more photoacid generator moieties having 4 or more carbon atoms.

In view thereof, reconsideration and withdrawal of the rejections are requested.

It is believed the application is in condition for immediate allowance, which action is earnestly solicited.

Respectfully submitted,

Date: March 1, 2023

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